IN THE SPECIFICATION

Please amend the paragraph starting at line 14 in page 11 of the specification as follows.

Part of a lithographic projection apparatus 2 according to a third embodiment of the invention is shown schematically and in cross-section in Figure 4. This embodiment of the invention additionally makes use of a sliding seal concept further described in European Patent Application No. 99201220.3 entitled "Motion Feed-Through into a Vacuum Chamber and its Application in Lithographic Apparatus" and a concurrently filed application of similar title (~~Applicant's ref: P-0130-010~~ U.S. Application No. 09/551,229) which are incorporated herein by reference. The vacuum chamber V is bounded by walls 11 which define an aperture 11a in the floor of the chamber. During use of the apparatus the vacuum chamber V is kept at a sufficient vacuum by vacuum pumps (not shown) of appropriate type. The aperture 11a is sealed by a sliding seal formed by sliding seal plate 12 in the middle of which is provided wafer support pillar 13. Pillar 13 supports the fine stage, or short stroke wafer support chuck, 14 which in turn carries the waver W.